

**Amendments to the Specification**

Please replace the paragraph beginning on page 16, last paragraph, and ending on page 17, line 13, with the following rewritten paragraph:

First, two glass substrates are prepared, and on one side of each of the surfaces of both glass substrates, a pattern comprising a monomolecular film (self-assembled film) is formed by the same method as in the first invention, using FAS 13. That is, the method of the first embodiment was applied to a liquid arranging surface 81 of a first substrate 8 and a thin-film-forming surface 71 of a second substrate 7 to form patterns 30a and 30b of a monomolecular film which have a same form when they were facing each other (cf. STEP 1 in figure 2). For example, a photomask, in which a round ultraviolet ray transmission part having the diameter of 50  $\mu\text{m}$  was reticularly arranged at the pitch of 5 mm, was used. By using such photomask, the monomolecular film patterns 30a and ~~30B~~30b also have a form in which a round opening 31 is reticularly arranged. Here, alignment marks were formed in the four corners of the photomask and such marks were transcribed to the monomolecular film patterns 30a and 30b, which is a preferred manner.